Measurement of the Central Atom (²⁹Si) Couplings in Triphenylsilyl and Related Radicals

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By γ -irradiation of the completely deuteriated compounds, $(C_6D_5)_nSiD_{3-n}$ (where n = 1-3), at 77 K, the anisotropic ²⁹Si couplings in the corresponding radicals, $(C_6D_5)_nSiD_{3-n}$, have been measured for the first time.

The triphenylmethyl (trityl) radical provides the archetypal example of a stable radical, and exists in solution in equilibrium with its *para*-quinoid dimer.¹ The very weak C–X bonds in a variety of triphenylmethyl compounds (Ph₃C–X)² are also in accord with particular stability of the trityl radical, which arises largely from its highly delocalised nature, as has been confirmed by ESR studies.³ The corresponding silicon centred radical is far more elusive, however; for instance, hexaphenyldisilane shows no sign of decomposition even at its melting point (268–370 °C).⁴ Bond dissociation energy measurements² indicate that Ph₃Si is *ca*. 8 kcal mol⁻¹ (1 cal =

4.184 J) more stable than Me₃Si and thus imply that there is a relatively weak stabilising interaction between the phenyl groups and the silicon radical centre.

There is no direct evidence available on this matter from ESR studies, since it has proved impossible, so far, to generate unsubstituted Ph_3Si radicals in fluid solution, although the sterically hindered analogues tris(3,5-di-*tert*-butylphenyl)silyl⁵ and trimesitylsilyl⁶ radicals have been observed, and appear to be partially (*ca.* 20%) delocalised species according to the ring proton hyperfine data.

The most direct measure of the configuration of a silicon

Table 1 Hyperfine coupling data for phenylsilyl and related radicals

Radical	A (²⁹ Si)/G ^a			
		\perp	iso	2 <i>B</i>
(C_6D_5) S iD ₂	218	144	169	49
(C ₆ D ₅)SiD	206	137	160	46
$(C_6D_5)_3$ Si	190	130	150	40
Me ₃ Si	233 ^b	155^{b}	181¢	52
Et ₃ Ši	221	_	170d	51
Bu ^t 3Si	215		163e	52

^{*a*} 1G = 10^{-4} T. ^{*b*} J. H. Sharp and M. C. R. Symons, *J. Chem. Soc. A*, 1970, 3084. ^{*c*} Ref. 8. ^{*d*} Ref. 9. ^{*e*} Ref. 10. All other data are from the present work.

radical centre is provided by the measurement of the ²⁹Si hyperfine coupling. In trimesitylsilyl,⁶ the isotropic splitting was measured at 135 G, and can be interpreted in terms of some delocalisation of the unpaired electron since it is reduced from the values typically found for trialkylsilyl radicals (Table 1). The complicating factor is that silyl radicals possess pyramidal configurations of the silicon centres:⁷ therefore, a reduction in the isotropic ²⁹Si splitting might reflect not only delocalisation of the unpaired electron but the adoption of a more planar configuration, leading in any case to a SOMO of lower silicon 3s character.

An alternative approach is to measure the ESR spectrum of the radical in a solid matrix so that the principal values of the ²⁹Si tensor are determined and from which may be extracted both the 3s and 3p orbital populations: thus details of the configuration of the radical centre and the degree of spindelocalisation are both obtained.

In our initial experiments, we studied γ -irradiated polycrystalline Ph₃SiH, but were unable to resolve ²⁹Si features since the spectral region in which they are present is obscured by the wings of the intense central signal from Ph₃Si radicals containing non-magnetic silicon nuclei. In order to reduce the linewidth of this central peak (approximately by a factor of 3.257, which is the ratio of H/D magnetic moments), we synthesised the fully deuteriated compound $(C_6D_5)_3SiD$ and recorded the ESR spectrum shown in the Fig. 1, following γ-irradiation, in which the parallel and perpendicular ²⁹Si features are clearly disclosed. Similarly, we have obtained the corresponding ²⁹Si hyperfine components in the radicals $(C_6D_5)_2$ SiD and C_6D_5 SiD₂ (Table 1) since we were also unable to detect clear ²⁹Si features in the ESR spectra obtained from the corresponding protic analogues Ph₂SiH₂ and PhSiH₃.

It is noteworthy that, at 150 G, the derived isotropic ²⁹Si coupling in $(C_6D_5)_3$ Si is greater than that in the trimesitylsilyl radical as measured in fluid solution.⁶ We consider that this is due to a steric effect where the more bulky mesityl groups force a more planar geometry at the radical centre. [The trend in isotropic ²⁹Si couplings in the series Me₃Si_,⁸ Et₃Si_,⁹ But₃Si¹⁰ (Table 1) probably reflects a similar effect.] Therefore, we believe that the present data provide a reliable representation of the electronic influence of phenyl substituents on a silicon centred radical. The anisotropic couplings (2B) reflect a reduction in the 3p spin population of *ca*. 0.23 by the three phenyl groups so that spin delocalisation is appreciable.

It is interesting to compare the p:s ratios that are obtained for the series $(C_6D_5)_3Si$, $(C_6D_5)_2SiD$, $(C_6D_5)_2SiD_2$: 5.07:1, 5.03:1, 4.66:1. Since the values relate only to a range of bond angles of 112.7–112.2° and are not therefore significantly different, the point is made that the increased delocalisation of the unpaired electron does not render the radical centre more planar, despite the implication of partial π -bonding between the phenyl groups and the silicon atom. If anything, the silicon centre is slightly more pyramidal when three phenyl groups



Fig. 1 (a) X-Band ESR spectrum recorded following γ -irradiation of $(C_6D_5)_3$ SiD showing ²⁹Si features from $(C_6D_5)_3$ Si radicals; (b) simulation using A_{\parallel} and A_{\perp} values given in the text along with $g_{\parallel} = 2.002$; $g_{\perp} = 2.006$; $\Delta H_{pp} = 18$ G

are present. This must relate to the substituent electronegativity effect which operates in the direction of increased bending, because carbon is more electronegative than silicon (the ratio of 5.03:1 in the Me₃Si radical implies that this is a more planar radical than is Ph₃Si, probably because of the greater electronegativity of an sp² than an sp³ carbon atom). The intrinsic energy barrier against making a silyl radical planar (13 kcal mol⁻¹)¹¹ is not overcome by the gain in delocalisation energy (*ca*. 2 kcal mol⁻¹ per phenyl group)². The former will be increased as the number of electronegative substituents increases and, according to the present results, dominates over the geometry that is chosen.

The case is similar to but less extreme than that for Cl substituents where it is clear that their increasing number profoundly decreases the Cl–Si–R bond angles at the radical centre, but delocalisation nonetheless increases along the series Me₂SiCl₁, MeSiCl₂, SiCl₃.¹²

There is one previous report that claims a determination of the ²⁹Si hyperfine tensor from an ESR study of an X-irradiated single crystal of Ph₃SiH.¹³ The paramagnetic species was assigned to a radical pair, and on the basis of the crystal orientation dependence of features assigned to ²⁹Si satellites, an isotropic coupling of *ca*. 80 G was derived, which is considerably lower than we measure in the present work. However, we believe that this reported value is incorrect, for the following reasons. Firstly, the features assigned to ²⁹Si lines appear to be at least five times too intense given the natural abundance of ²⁹Si (4.7%). Secondly, it does not seem reasonable that the isotropic coupling in Ph₃Si should be so

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dramatically lower than that in trimesitylsilyl (135 G; as explained earlier, the converse is more reasonable), particularly by comparison of the series Me₃Si, Ph₃Si, Mes₃Si [$a(^{29}Si)$ 181 G,⁸ 79.6 G,¹³ 135 G⁶] with the corresponding germanium centred radicals, Me₃Ge, Ph₃Ge, Mes₃Ge [a(Ge) 84.7 G,¹⁴ 84 G,¹⁵ 68.4 G⁶]. In contrast, our value of $a(^{29}Si)$ for Ph₃Si, at 150 G, is in good accord with these data.

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